



PATENT
Customer No. 22,852
Attorney Docket No. 3180.0356

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)	
)	
TAKASHI SATO ET AL.)	
)	
Application No.: 10/781,652)	Group Art Unit: 2851
)	
Filed: February 20, 2004)	Examiner: D. Rutledge
)	
For: LITHOGRAPHY SIMULATION)	Confirmation No.: 3464
METHOD, MASK PATTERN)	
CORRECTION METHOD, AND)	
SUBSTRATE TOPOGRAPHY)	
CORRECTION METHOD)	

Mail Stop Issue Fee
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

RESPONSE TO EXAMINER'S STATEMENT

Attached to the Notices of Allowance and Allowability dated August 15, 2005, under the section entitled "Information Disclosure Statement," the Examiner indicated that the Japanese reference (JP 2002-6475) "was reviewed based on the drawings since a translation was not provided."

JP 2002-6475 was submitted to the Patent Office in the Information Disclosure Statement ("IDS") filed February 9, 2005. In that IDS, Applicants pointed out that the relevance of JP 2002-6475 is discussed in their patent application at page 1. That discussion at page 1 explains the aspects of conventional lithography to which JP 2002-

6475 is directed. At least in view of that discussion, JP 2002-6475 is not material to the patentability of the present application.

If there is any fee due in connection with the filing of this Response, please charge the fee to our Deposit Account No. 06-0916.

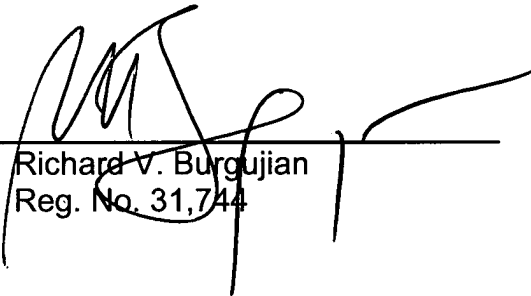
Respectfully submitted,

FINNEGAN, HENDERSON, FARABOW,
GARRETT & DUNNER, L.L.P.

Dated: _____

10/14/05

By: _____


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